

INFORMATION DISCLOSURE STATEMENT BY APPLICANT(S)

(Use as many sheets as necessary)

Sheet 1 of 3

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Examiner

Initials*

COMPLETE IF KNOWN						
Application Number	10/533,822					
Filing Date	August 31, 2005					
First Named Inventor	Mino Green					
Art Unit	2815					
Examiner Name	Jami M. Valentine					
Attorney Docket No.	KSTR 2 00004					

Applicant of Cited Document

	U.S. PATENT	DOCUMENTS
Document No. Number-Kind Code ^(if known)	Publication Date MM-DD-YYYY	Name of Patentee of Applicant of Cited Docu

FOREIGN PATENT DOCUMENTS								
Examiner	Cite	Foreign Patent Document	Publication Date	Name of Patentee or	Т			
Initials*	No.	Country Code-Number Kind Code (if known)	MM-DD-YYYY	Applicant of Cited Document				
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Form 1449/PTO					COMPLETE IF KNOWN			
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